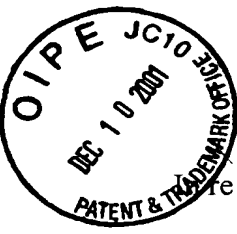


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D. Bell



Express Mail No.: EL 340 685 032 US

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Re Application of:
RANISH, Joseph M.

Serial No.: 09/595,765

Group Art Unit: 2875

Filed: June 16, 2000

Examiner: Bao Q. Truong

For: **LAMPHEAD FOR A RAPID
THERMAL PROCESSING CHAMBER**

Attorney Docket No.: 003998
(10732-0044-99)

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AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Applicants submit the following Amendment in response to the Office Action mailed July 30, 2001, in the above identified application.

2 Month Extension of Time. Pursuant to 37 C.F.R. 1.136(a), the Applicant hereby petitions for a 2-month extension of time to respond to the Office Action mailed July 30, 2001. This extension will extend the response due date to December 30, 2001.

Please amend the application as follows:

In the Specification:

Marked up versions of all revised paragraphs, showing insertions and deletions, are included in Appendix A.

Replace the paragraph at page 5, line 10, with the following text:

al
An RTP system that has been modified in accordance with the invention is shown in Figures 1-2. The RTP system includes a processing chamber 100 for processing a disk-shaped, eight inch (200 mm) or twelve inch (300 mm) diameter silicon substrate 106. The substrate 106 is mounted inside the chamber on a substrate support structure 108 and is heated by a heating element or a monolithic lamphead-reflector 202 located above the substrate. The heating element 202 generates radiation 112 which is directed to a front side of the substrate and which enters the processing chamber 100 through a water-cooled quartz